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Process Research in Thin Film and Coating Technology

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Message from the Guest Editors

This Special Issue is dedicated to "Process Research in Thin Film and Coating Technology". The aim is to bring together scientists working on the technology of membranes and coatings from several disciplines to further develop new methods and ideas.

The topics to be covered include (but are not limited to):

- Polymers, metals, alloys, and composites for membranes and coatings;
- Novel materials for membranes and coatings;
- Synthesis and characterization of membranes and coatings;
- Industrial processes;
- Thermodynamics and transport properties;
- Theory and simulations;
- Applications.











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Message from the Editor-in-Chief

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